

(b) Operations similar to electroplating which are specifically excepted from coverage of this part include:

(1) Electrowinning and electrorefining conducted as a part of nonferrous metal smelting and refining (40 CFR part 421);

(2) Metal surface preparation and conversion coating conducted as a part of coil coating (40 CFR part 465);

(3) Metal surface preparation and immersion plating or electroless plating conducted as a part of porcelain enameling (40 CFR part 466); and

(4) Electrodeposition of active electrode materials, electroimpregnation, and electroforming conducted as a part of battery manufacturing (40 CFR part 461).

(c) Metallic platemaking and gravure cylinder preparation conducted within or for printing and publishing facilities, and continuous strip electroplating conducted within iron and steel manufacturing facilities which introduce pollutants into a publicly owned treatment works are exempted from the pretreatment standards for existing sources set forth in this part.

(Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, 33 U.S.C. 1251 *et. seq.*, as amended by the Clean Water Act of 1977, Pub. L. 95-217))

[46 FR 9467, Jan. 28, 1981, as amended at 48 FR 32482, July 15, 1983; 48 FR 41410, Sept. 15, 1983; 51 FR 40421, Nov. 7, 1986]

#### § 413.02 General definitions.

In addition to the definitions set forth in 40 CFR part 401 and the chemical analysis methods set forth in 40 CFR part 136, both of which are incorporated herein by reference, the following definitions apply to this part:

(a) The term *CN,A* shall mean cyanide amenable to chlorination as defined by 40 CFR 136.

(b) The term *CN,T* shall mean cyanide, total.

(c) The term *Cr,VI* shall mean hexavalent chromium.

(d) The term *electroplating process wastewater* shall mean process wastewater generated in operations which are subject to regulation under any of subparts A through H of this part.

(e) The term *total metal* is defined as the sum of the concentration or mass of Copper (Cu), Nickel (Ni), Chromium (Cr) (total) and Zinc (Zn).

(f) The term *strong chelating agents* is defined as all compounds which, by virtue of their chemical structure and amount present, form soluble metal complexes which are not removed by subsequent metals control techniques such as pH adjustment followed by clarification or filtration.

(g) The term *control authority* is defined as the POTW if it has an approved pretreatment program; in the absence of such a program, the NPDES State if it has an approved pretreatment program or EPA if the State does not have an approved program.

(h) The term *integrated facility* is defined as a facility that performs electroplating as only one of several operations necessary for manufacture of a product at a single physical location and has significant quantities of process wastewater from non-electroplating manufacturing operations. In addition, to qualify as an “integrated facility” one or more plant electroplating process wastewater lines must be combined prior to or at the point of treatment (or proposed treatment) with one or more plant sewers carrying process wastewater from non-electroplating manufacturing operations.

(i) the term *TTO* shall mean total toxic organics, which is the summation of all quantifiable values greater than 0.01 milligrams per liter for the following toxic organics:

Acenaphthene  
Acrolein  
Acrylonitrile  
Benzene  
Benzidine  
Carbon tetrachloride (tetrachloromethane)  
Chlorobenzene  
1,2,4-trichlorobenzene  
Hexachlorobenzene  
1,2-dichloroethane  
1,1,1-trichloroethane  
Hexachloroethane  
1,1-dichloroethane  
1,1,2-trichloroethane  
1,1,2,2-tetrachloroethane  
Chloroethane  
Bis (2-chloroethyl) ether  
2-chloroethyl vinyl ether (mixed)  
2-chloronaphthalene  
2,4,6-trichlorophenol  
Parachlorometa cresol

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Chloroform (trichloromethane)  
2-chlorophenol  
1,2-dichlorobenzene  
1,3-dichlorobenzene  
1,4-dichlorobenzene  
3,3-dichlorobenzidine  
1,1-dichloroethylene  
1,2-trans-dichloroethylene  
2,4-dichlorophenol  
1,2-dichloropropane  
1,3-dichloropropylene (1,3-dichloropropene)  
2,4-dimethylphenol  
2,4-dinitrotoluene  
2,6-dinitrotoluene  
1,2-diphenylhydrazine  
Ethylbenzene  
Fluoranthene  
4-chlorophenyl phenyl ether  
4-bromophenyl phenyl ether  
Bis (2-chloroisopropyl) ether  
Bis (2-chloroethoxy) methane  
Methylene chloride (dichloromethane)  
Methyl chloride (chloromethane)  
Methyl bromide (bromomethane)  
Bromoform (tribromomethane)  
Dichlorobromomethane  
Chlorodibromomethane  
Hexachlorobutadiene  
Hexachlorocyclopentadiene  
Isophorone  
Naphthalene  
Nitrobenzene  
2-nitrophenol  
4-nitrophenol  
2,4-dinitrophenol  
4,6-dinitro-o-cresol  
N-nitrosodimethylamine  
N-nitrosodiphenylamine  
N-nitrosodi-n-propylamine  
Pentachlorophenol  
Phenol  
Bis (2-ethylhexyl) phthalate  
Butyl benzyl phthalate  
Di-n-butyl phthalate  
Di-n-octyl phthalate  
Diethyl phthalate  
Dimethyl phthalate  
1,2-benzanthracene  
(benzo(a)anthracene)  
Benzo(a)pyrene (3,4-benzopyrene)  
3,4-Benzofluoranthene  
(benzo(b)fluoranthene)  
11,12-benzofluoranthene  
(benzo(k)fluoranthene)  
Chrysene  
Acenaphthylene  
Anthracene  
1,12-benzoperylene  
(benzo(ghi)perylene)  
Fluorene  
Phenanthrene  
1,2,5,6-dibenzanthracene  
(dibenzo(a,h)anthracene)  
Indeno (1,2,3-cd) pyrene)  
(2,3-o-phenylene pyrene)  
Pyrene  
Tetrachloroethylene

Toluene  
Trichloroethylene  
Vinyl chloride (chloroethylene)  
Aldrin  
Dieldrin  
Chlordane (technical mixture and metabolites)  
4,4-DDT  
4,4-DDE (p,p-DDX)  
4,4-DDD (p,p-TDE)  
Alpha-endosulfan  
Beta-endosulfan  
Endosulfan sulfate  
Endrin  
Endrin aldehyde  
Heptachlor  
Heptachlor epoxide  
(BHC-hexachlorocyclohexane)  
Alpha-BHC  
Beta-BHC  
Gamma-BHC  
Delta-BHC  
(PCB-polychlorinated biphenyls)  
PCB-1242 (Arochlor 1242)  
PCB-1254 (Arochlor 1254)  
PCB-1221 (Arochlor 1221)  
PCB-1232 (Arochlor 1232)  
PCB-1248 (Arochlor 1248)  
PCB-1260 (Arochlor 1260)  
PCB-1016 (Arochlor 1016)  
Toxaphene  
2,3,7,8-tetrachlorodibenzo-  
p-dioxin (TCDD)  
(Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, 33 U.S.C. 1251 *et. seq.*, as amended by the Clean Water Act of 1977, Pub. L. 95-217))  
[46 FR 9467, Jan. 28, 1981, as amended at 48 FR 32483, July 15, 1983; 48 FR 43681, Sept. 26, 1983; 51 FR 40421, Nov. 7, 1986]

### § 413.03 Monitoring requirements.

(a) In lieu of monitoring for TTO, the control authority may allow industrial users of POTWs to make the following certification as a comment to the periodic reports required by § 403.12(e): "Based on my inquiry of the person or persons directly responsible for managing compliance with the pretreatment standard for total toxic organics (TTO), I certify that, to the best of my knowledge and belief, no dumping of concentrated toxic organics into the wastewaters has occurred since filing the last discharge monitoring report. I further certify that this facility is implementing the toxic organic management plan submitted to the control authority."

(b) In requesting that no monitoring be required industrial users of POTWs